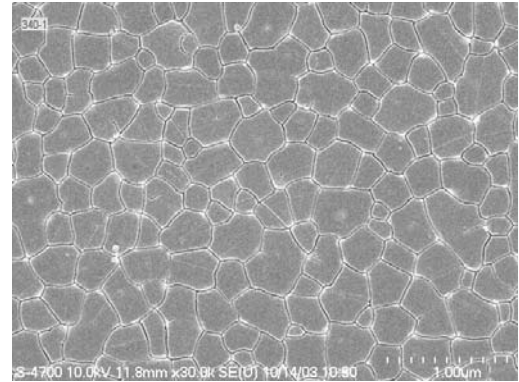
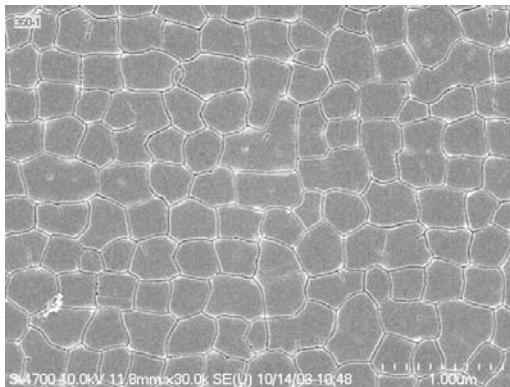


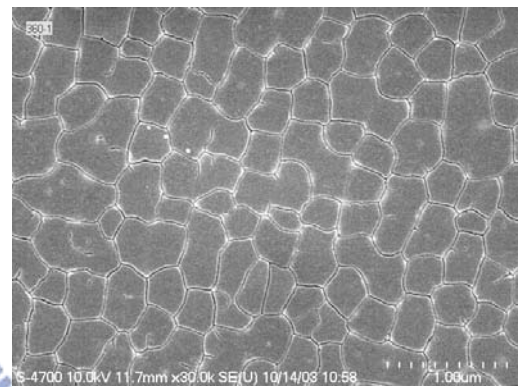
(a)



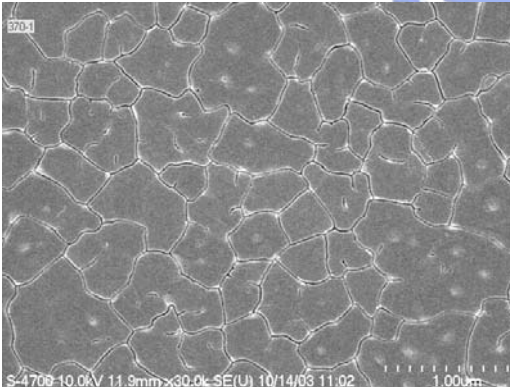
(b)



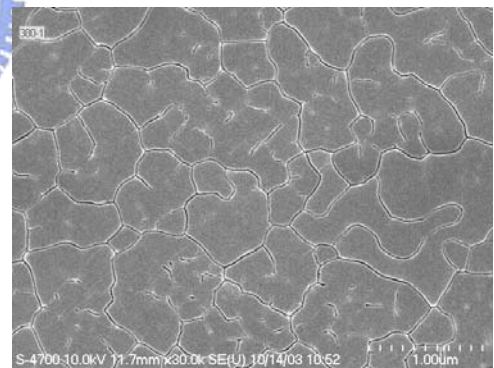
(c)



(d)

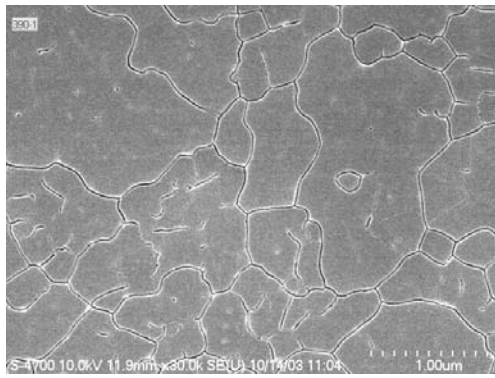


(e)

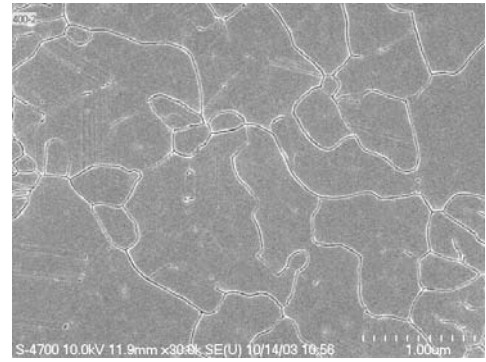


(f)

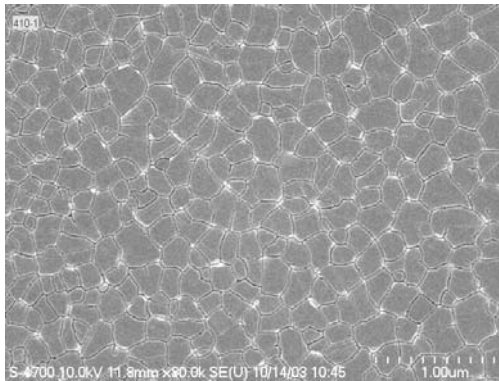
Fig. 3-15 SEM micrographs of excimer laser crystallized poly-Silicon films after Secco etching for 60sec treatment. The applied laser energy densities are (a) 330, (b) 340, (c) 350, (d) 360 (e) 370 (f) 380 mJ/cm^2 . The laser energy 900mJ, frequency 300Hz, power 230W, scan speed 6mm/sec, pitch 0.02mm, beam width 0.4mm, pre treatment clean with HF+O₃



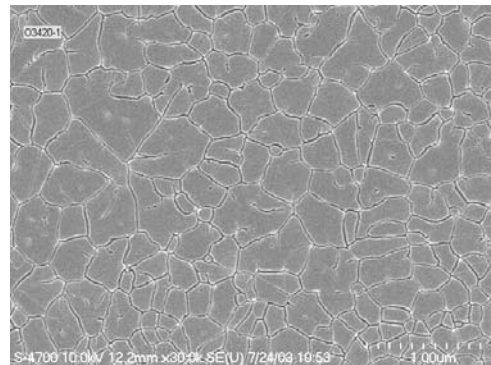
(a)



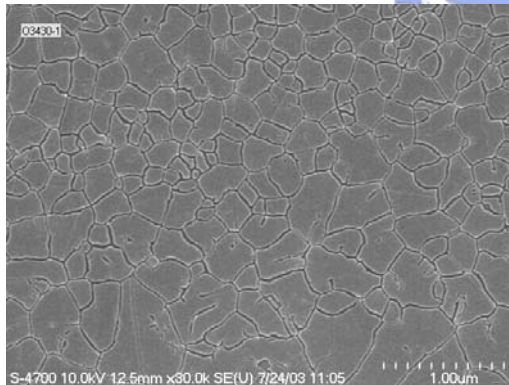
(d)



(b)



(e)



(c)

Fig. 3-16 SEM micrographs of excimer laser crystallized poly-Silicon films after Secco etching for 60sec treatment. The applied laser energy densities are (a) 390, (b) 400, (c) 410, (d) 420 (e) 430 mJ/cm^2 . The laser energy 900mJ, frequency 300Hz, power 230W, scan speed 6mm/sec, pitch 0.02mm, beam width 0.4mm, pre treatment clean with HF+O₃